

P27374.A06

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants : Dureseti CHIDAMBARRAO, et al. Group Art Unit: 2814  
Appln. No. : 10/605,108 Examiner: PHAM, Long  
Filed : September 9, 2003 Confirmation No. 2107  
For : METHOD FOR REDUCED N+ DIFFUSION IN STRAINED SI  
ON SI/GE SUBSTRATE

**AMENDMENT UNDER 37 C.F.R. 1.111**

Commissioner for Patents  
U.S. Patent and Trademark Office  
Customer Window, Mail Stop Amendment  
Randolph Building  
401 Dulany Street  
Alexandria, VA 22314  
Sir:

Responsive to the non-final Official Action of December 28, 2005,  
reconsideration and withdrawal of the rejections made therein are respectfully  
requested, in view of the following amendments and remarks.

Amendments to the claims begin on page 2; and

Remarks begin on page 7.

Inasmuch as the Official Action sets a three-month shortened statutory period  
which expires March 28, 2006, this Amendment is being timely filed and no extension of  
time is believed necessary. However, if an extension is deemed by the Patent and  
Trademark Office to be necessary, the same is hereby requested and the Patent and  
Trademark Office is hereby authorized to charge any necessary fees in connection  
therewith or any fees necessary to preserve the pendency of this application to deposit  
account No. 09-0458.